

Layer-by-layer assembly and intercalation reactions of iron(III) and iron(II) alkanebisphosphonates on gold surfaces

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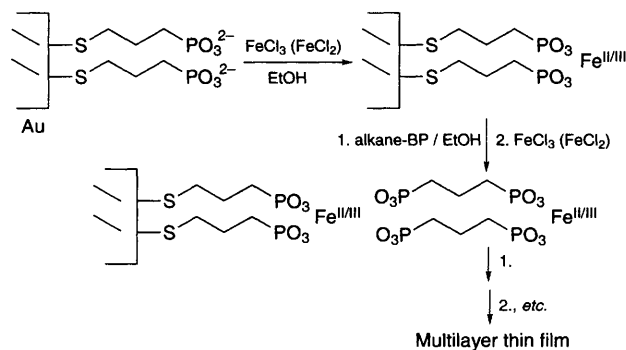
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Multilayer films of Fe³⁺ and Fe²⁺ alkanebisphosphonates are assembled on gold surfaces, and the Fe³⁺ is found to oxidize pyrrole to produce mono/multilayer quantities of poly(pyrrole).

Transition-metal phosphates and phosphonates are lamellar solids with chemical and physical properties that make them potentially useful in such diverse applications as catalysis,¹ chemical sensing,² chiral separations,³ ion exchange⁴ and optics.⁵ Recently, new lamellar Fe²⁺ and Fe³⁺ phosphonates, Fe(RPO₃)·H₂O, HFe(RPO₃)₂·H₂O and HFe(RPO₃H)₄, were synthesized by reacting FeOCl with alkyl- and aryl-phosphonic acids.^{5–7} The resulting bulk materials have displayed interesting optical^{5a} and magnetic⁶ properties.

In an effort to modify rationally the chemical properties of solid surfaces, we and others have previously developed techniques for growing mono- and multi-layer thin films of metal (Zr⁴⁺, Hf⁴⁺, Ln³⁺, Al³⁺, Cu²⁺, Zn²⁺, Mn²⁺) organophosphonates on solid supports.^{8–10} These methods involve sequential complexation reactions of a bisphosphonic acid and the metal cation from separate aqueous or non-aqueous solutions. The present communication describes an extension of this method to the synthesis of Fe³⁺ and Fe²⁺ alkanebisphosphonate thin films. To our knowledge, the Fe³⁺ films represent the first examples of phosphonate thin films that possess an electroactive metal ion within the layers. While the Fe³⁺ centres do not appear to be addressable electrochemically, we have found that they can initiate the oxidative polymerization of pyrrole to form a monolayer or even multilayer quantities of poly(pyrrole).

The preparation of Fe³⁺-alkanebisphosphonate (Fe³⁺-BP) thin films is shown in Scheme 1. A clean gold substrate† (EMF, Inc.) was placed in an EtOH solution containing 1 μg ml⁻¹ of H₂O₃PC₄H₈SSC₄H₈PO₃H₂ for 24 h, in order to anchor the subsequently grown films to the surface. Multilayer Fe³⁺-BP growth was accomplished by alternately immersing the substrate in a solution containing FeCl₃ (0.1 mol dm⁻³ in EtOH) followed by immersion in a solution of the desired alkanebisphosphonate (1 mmol dm⁻³ in EtOH) for 2 h each. Longer immersion times resulted in no further increase in film



Scheme 1 Synthesis of Fe^{II/III} alkanebisphosphonate multilayer films

thickness. Identical procedures were used to grow Fe²⁺-BP thin films using FeCl₂ in EtOH.

Iron phosphonate film growth was monitored by thin-film ellipsometry.† Typical plots of film thickness vs. layer number for C₁₀ and C₁₆ Fe³⁺ alkanebisphosphonates are shown in Fig. 1. The plots are linear with slopes of 19.0, 16.8 and 15.4 Å per layer for the C₁₆, C₁₄ and C₁₀ bisphosphonates, respectively (the C₁₄ data were excluded for clarity). Linear plots are also observed in the ellipsometry data of Fe²⁺ C₁₀-BP films [Fig. 1(b)].

Layer-by-layer assembly is further confirmed by monitoring the CH₂ stretches of the alkyl group (asymmetric stretch λ_{max} 2852 cm⁻¹, symmetric stretch λ_{max} 2926 cm⁻¹) with reflectance FTIR spectroscopy (Nicolet model 730). A linear increase in absorbance vs. layer number was observed for the Fe³⁺ C₁₀-BP. The presence of OH stretching vibrations of the POH group at 3040–3315 cm⁻¹ is consistent with possible formulations of the film as HFe(C₁₀-BP)·H₂O or HFe(C₁₀-BP)₂.^{6,7}

The composition of Fe³⁺-C₁₀ BP films was investigated with X-ray photoelectron spectroscopy (XPS). Although the iron oxidation state could not be determined unambiguously by

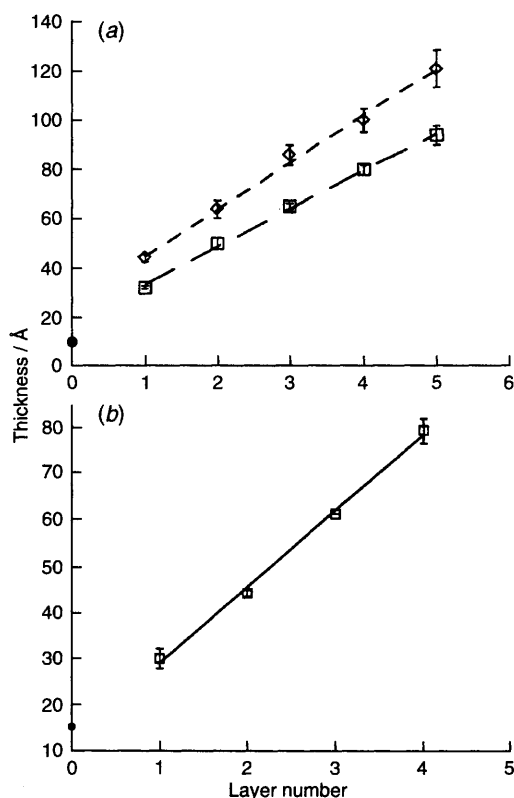


Fig. 1 (a) Ellipsometric film thickness vs. layer number for Fe³⁺ alkanebisphosphonate films; (●) sulfanylethylamine, (◇) Fe³⁺ + C₁₆-BP, (□) Fe³⁺ + C₁₀-BP. Each layer was terminated with Fe³⁺. (b) Film thickness vs. layer number for Fe²⁺ C₁₀-BP. The error bars represent the deviations of five measurements taken in different locations on the surface.

XPS, the Fe:P peak area ratios for phosphate- and Fe³⁺-terminated films were determined and compared with ratios calculated^{9a} based on HFe(C₁₀-BP)₂ and HFe(C₁₀-BP)·H₂O structural models. As shown in Table 1, the calculated values are consistent with the 4:1 Fe:P stoichiometry.

The Fe³⁺ in the Fe³⁺-BP salts can be used to initiate the oxidative polymerization of adsorbed pyrrole vapour. This is accomplished by simply placing the film in a closed container above neat liquid pyrrole. In 24 h, the ellipsometric film thickness increased by ca. 5 Å per Fe³⁺ layer contained in the film, presumably due to the reaction of Fe³⁺ with pyrrole to yield poly(pyrrole) and Fe²⁺. The presence of poly(pyrrole) polymerized onto a monolayer of Fe³⁺ C₁₀-BP was detected electrochemically (Fig. 2). For the film shown in Fig. 2, the anodic peak current was found to scale linearly with scan rate indicating a surface-bound redox interconversion.¹² No growth of polypyrrole was detected by ellipsometry in the case of the

Table 1 Normalized Fe:P XPS peak area ratios for three-layer Fe³⁺ C₁₀-BP films

	Fe ³⁺ terminated	C ₁₀ -BP terminated
Fe:P (obs.)	1.0	0.57
HFe(C ₁₀ -BP) ₂ Fe:P calc. ^a	0.80	0.57
HFe(C ₁₀ -BP)·H ₂ O Fe:P calc. ^a	1.6	0.12

^a Normalized Fe:P peak area ratios were calculated using electron mean free paths of 68 and 44 Å, and atomic sensitivity factors of 0.412 and 2.87 for P and Fe, respectively (see ref. 9a for details).

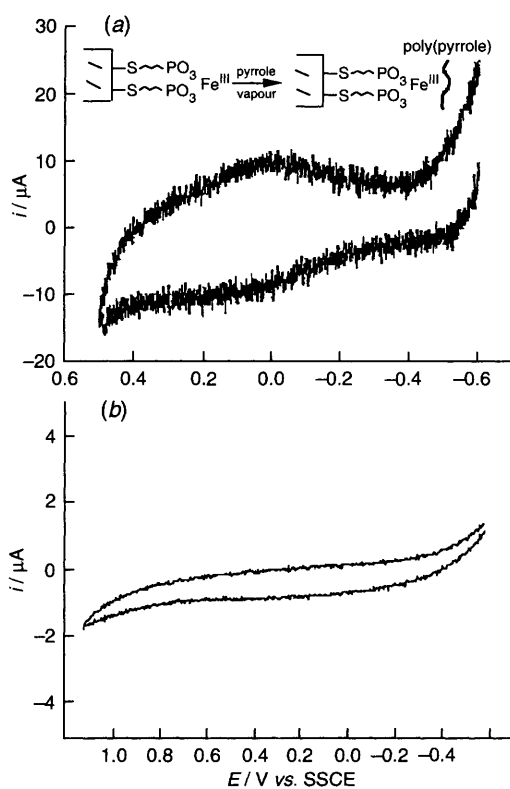


Fig. 2 (a) Cyclic voltammogram of one layer of Fe³⁺ phosphonate which had previously been exposed to pyrrole vapour and (b) of five layers of Fe³⁺ C₁₀-BP not exposed to pyrrole vapour; solvent MeCN–0.1 mol dm⁻³ NBu₄PF₆, the auxiliary electrode was a platinum wire and the reference was a saturated calomel electrode. Scan rate 100 mV s⁻¹.

Fe²⁺-BP films, consistent with the weaker oxidizing power of Fe²⁺.

We have described a method for multilayer film growth of Fe³⁺ and Fe²⁺ alkanebisphosphonates on solid surfaces based on sequential complexation reactions. This technique allows the rational design of surfaces with a material that is potentially useful for catalysis, electrocatalysis, magnetic applications and optical waveguides. Additionally, thin films of Fe³⁺ can be used to synthesize monolayers of conducting polymer films. This represents an alternate route to conducting polymer thin films to that described first by Simon *et al.* and more recently by Willicut and McCarley, in which monolayer-forming pyrrole derivatives were electropolymerized on silicon and gold surfaces.¹³ We are currently examining the conductive properties of the polymer–iron bisphosphonate intercalation compounds.

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Footnotes

† Gold substrates were cleaned by dipping in H₂SO₄–H₂O₂ (3:1) for ca. 2 min followed by sonication in ethanol (95%) and deionized H₂O.

‡ Ellipsometric measurements were made with a Rudolf 437 ellipsometer as described previously.¹¹

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